

TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT
(Under 37 CFR 1.97(b) and 1.97(e))

Docket No.
0SBE-101519

In Re Application Of: **Rahul Ganguli et al.**

SEP 03 2004

Application No.

10/646,356

Filing Date

August 22, 2003

Not yet assigned

Customer No.

30764

Group Art Unit

1752

Confirmation No.

8611

Title: **PHOTOMASK ASSEMBLY INCORPORATING A POROUS FRAME AND METHOD
FOR MAKING IT**

Address to:

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

37 CFR 1.97(b)

1. ☒ The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits, or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114.

37 CFR 1.97(c)

2. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), provided that the Information Disclosure Statement is filed before the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by one of:

☐ the statement specified in 37 CFR 1.97(e);

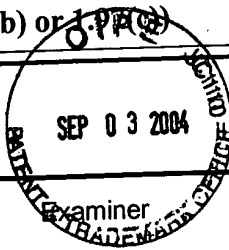
OR

☐ the fee set forth in 37 CFR 1.17(p).

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Payment of Fee

(Only complete if Applicant elects to pay the fee set forth in 37 CFR 1.17(p))

- ☐ A check in the amount of _____ is attached.
- ☒ The Director is hereby authorized to charge and credit Deposit Account No. 19-1853 as described below.
- ☐ Charge the amount of _____
- ☐ Credit any overpayment.
- ☒ Charge any additional fee required.
- ☐ Payment by credit card. Form PTO-2038 is attached.

WARNING: Information on this form may become public. Credit card information should not be included on this form. Provide credit card information and authorization on PTO-2038.

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Signature

James R. Brueggemann, Esquire

Registration No. 28, 286

Sheppard, Mullin, Richter & Hampton LLP

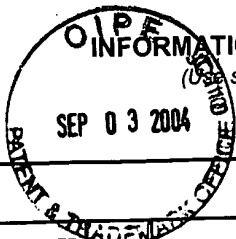
333 South Hope Street, 48th Floor

Los Angeles, California 90071

(213) 620-1780

Dated: August 31, 2004

CC:

**INFORMATION DISCLOSURE CITATION**

(Use several sheets if necessary)

ATTY DOCKET NO.

OSBE-101519

APPLICATION NO.

10/646.356

APPLICANT(S)

Rahul Ganguli et al.

FILING DATE

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GROUP ART UNIT

1752

U.S. PATENT DOCUMENTS

| *EXAMINER INITIAL | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE IF APPROPRIATE |
|----------------------|-----------------|----------|----------------|-------|----------|-------------------------------|
| | 4,833,051 | 05/23/89 | Imamura | 430 | 5 | |
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FOREIGN PATENT DOCUMENTS

| | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | TRANSLATION | |
|--|-----------------|----------|---------|-------|----------|-------------|----|
| | | | | | | YES | NO |
| | WO 01/59522 A1 | 08/16/01 | PCT | | | | |
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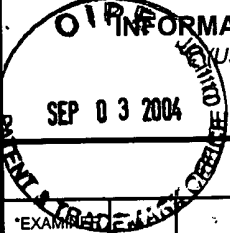
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

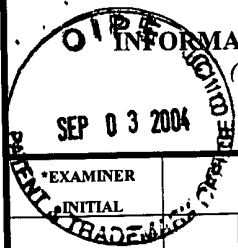
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| | | Kikugawa, S., Okada, K., Mishiro, H. and Sasuga, T., "Current Status of Hard Pellicle Development, <u>Asahi Glass Co., Ltd.</u> , December 10, 2001, pp 1-14 |
| | | Laganza, Joseph, "157nm Reticle Handling Technology, <u>Sematech TDR</u> , December 12, 2001, pp 1-20 |

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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|--|--|-----------------|---|---------------------------------------|------------------------|--------------------------------------|-------------------------------|----|
|  <p>INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p> | | | | ATTY DOCKET NO. OSBE-101519 | | APPLICATION NO. 10/646,356 | | |
| | | | | Rahul Ganguli et al. | | | | |
| | | | | FILING August 22, 2003 | | GROUP ART 1752 | | |
| U.S. PATENT DOCUMENTS | | | | | | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | | |
| | | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | TRANSLATION | |
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| EXAMINER | | | | | DATE CONSIDERED | | | |
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Meixner, D. Laurence, et al., "Porous silica frame for deep UV lithography," Proceedings of SPIE, Vol. 4889, October 3, 2002, pp 450-456

Bhattacharyya, Kaustuve, et al., "Investigation of reticle defect formation at DUV lithography," Photomask, February 2003, Vol. 19, Issue 2, 7 pages

Meixner, D. Laurence, "Porous silica frame for deep UV lithography," Proceedings of SPIE, Vol. 5040, February 25, 2003, pp 1018-1024

Jeng, De-Yin, et al., "Porous Silica Pellicle Frame," Proceedings of SPIE, Vol. 5256, September 9, 2003, pp 213-221

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